

Micron Internship Final Presentation

Application of Machine Learning and KNN Algorithm to Predict Ideal WIP

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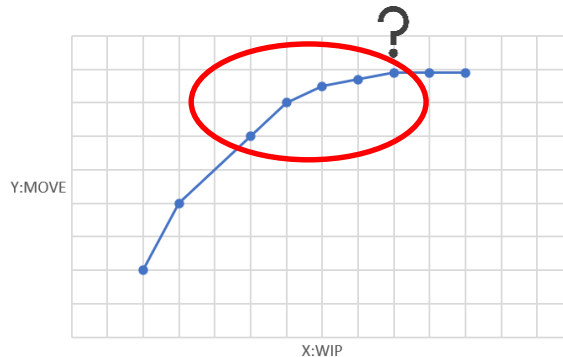
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01. Introduction

- During wafer fabrication, process data, equipment data will be automatically recorded and accumulated in database for monitoring the process, diagnosing faults.
- However, in semiconductor manufacturing industry, many factors that are interrelated affect the yield of fabricated wafers.
- Therefore, this study uses Machine Learning methods to analyze when WIP raise to a certain level, MOVE will approach saturation.



01. Introduction

- **Purpose:** Hope to find ideal WIP through Machine Learning methods.
- **Methods:** Using KNN algorithm and data analysis process to analyze and predict ideal WIP.
- **Analysis Tools:** Python 、 SQL 、 Excel
- **Why choose KNN model? (R squared, MSE...)**
- **What are the analysis variables? (WIP, MOVE)**
- **How many data do we need in this research?**
(One year data)

| | R squared | MSE | Data type |
|---------------------------|-----------|------|-----------|
| K Nearest Neighbors | 0.93 | 0.69 | Nonlinear |
| Linear Regression | 0.65 | 3.67 | linear |
| Support Vector Regression | 0.78 | 2.26 | Nonlinear |

02. Literature Review - KNN algorithms



KK Nearest Neighbors(KNN)

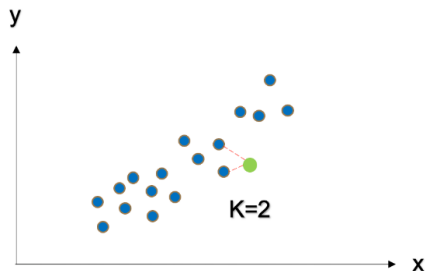
It belongs to one of the algorithms of Supervised learning in Machine learning.



Pros : The biggest advantage of k-NN is that it is easy to understand, and the performance is reasonable without too much adjustment.



Cons : The construction of the k-NN model is fast, but the prediction speed is slow when the number of features or data points in the training data is large.



| identifier | class name | args | distance function |
|---------------|---------------------|---------|------------------------------------|
| "euclidean" | EuclideanDistance | • | $\sqrt{\sum (x - y)^2}$ |
| "manhattan" | ManhattanDistance | • | $\sum x - y $ |
| "chebyshev" | ChebyshevDistance | • | $\max(x - y)$ |
| "minkowski" | MinkowskiDistance | p | $\sum x - y ^p^{(1/p)}$ |
| "wminkowski" | WMinkowskiDistance | p, w | $\sum w * (x - y) ^p^{(1/p)}$ |
| "seuclidean" | SEuclideanDistance | V | $\sqrt{\sum ((x - y)^2 / V)}$ |
| "mahalanobis" | MahalanobisDistance | V or VI | $\sqrt{((x - y)' V^{-1} (x - y))}$ |

02. Literature Review - KNN algorithms

Evaluation Matrix : **MSE** 、 **R Square**

$$MSE(y, \hat{y}) = \frac{1}{n} \sum_{i=1}^n (y_i - \hat{y}_i)^2$$

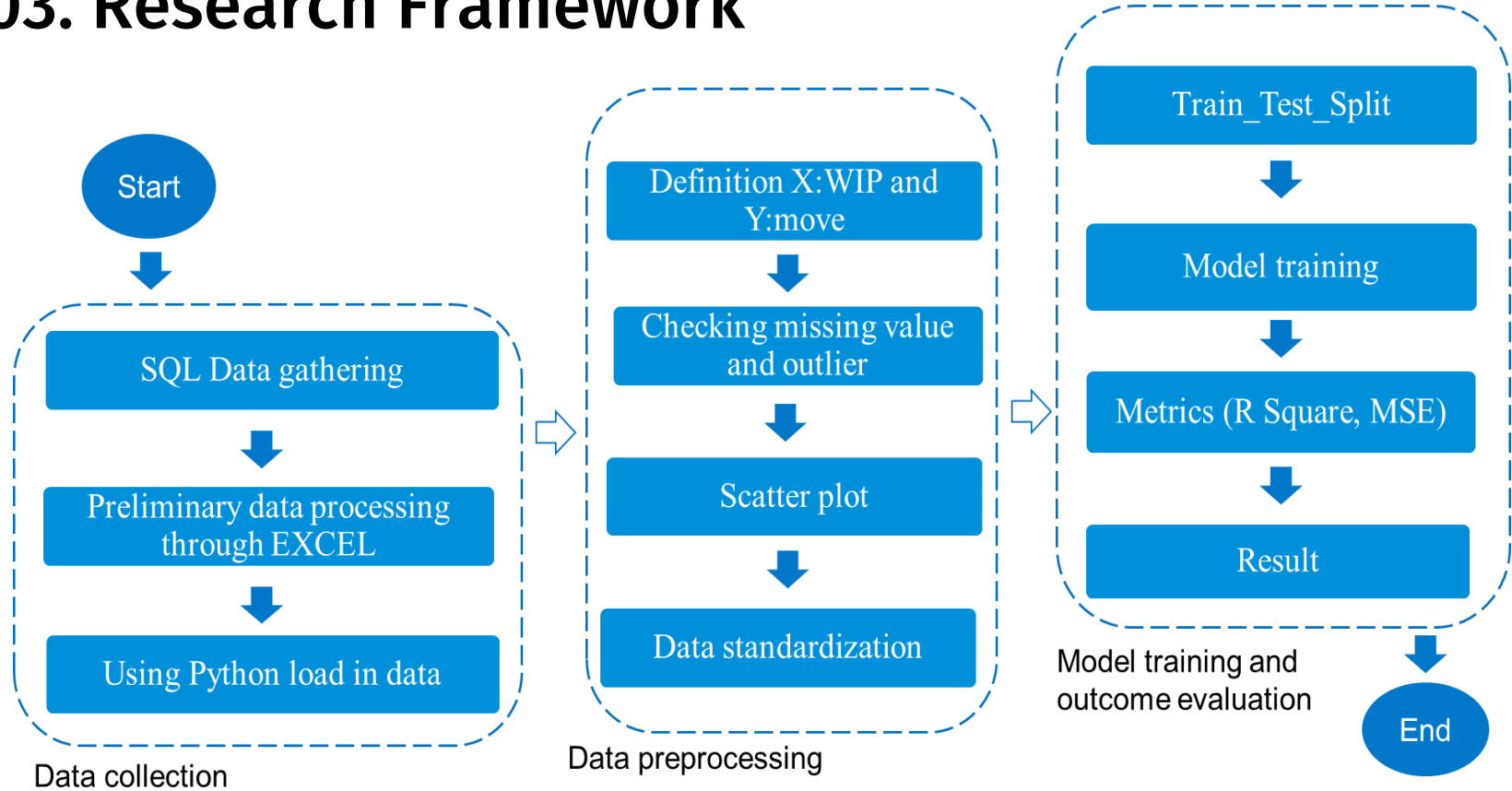
MSE (Mean-Square Error) The smaller the error, the better ◦

$$R^2(y, \hat{y}) = 1 - \frac{\sum_{i=1}^n (y_i - \hat{y}_i)^2}{\sum_{i=1}^n (y_i - \bar{y})^2}$$

R Square (coefficient of determination): The coefficient is between 0 and 1, and it is used to explain the percentage of explained variation in the total variation. The closer to 1 is the better.

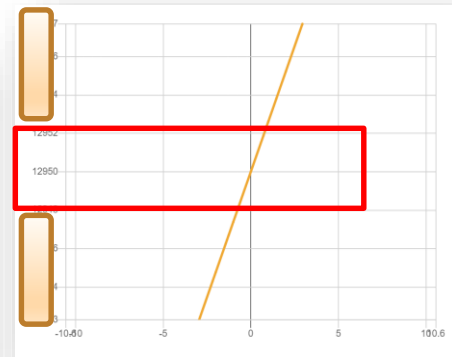
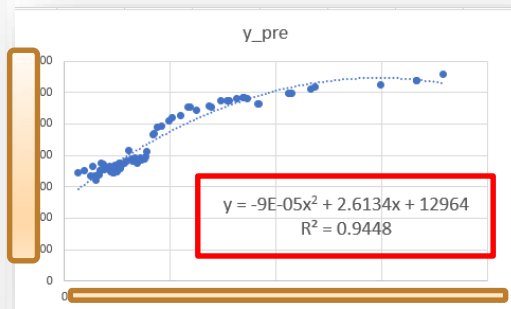
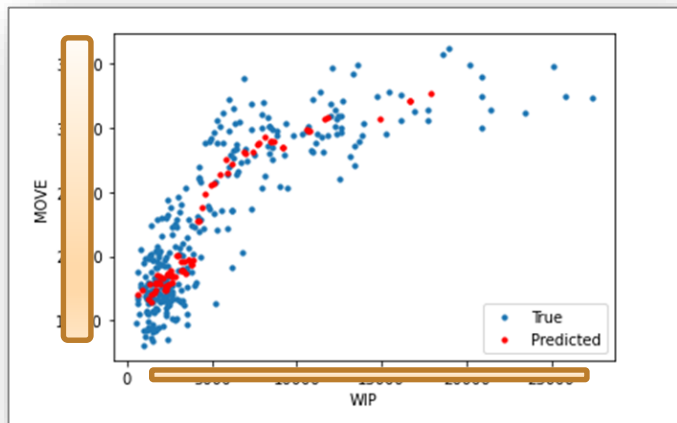
(R2 > 0.8 are highly reliable)

03. Research Framework



04. Experimental Results

This is one of the **Dry Etch bottleneck work stations**, as the research object of this time.

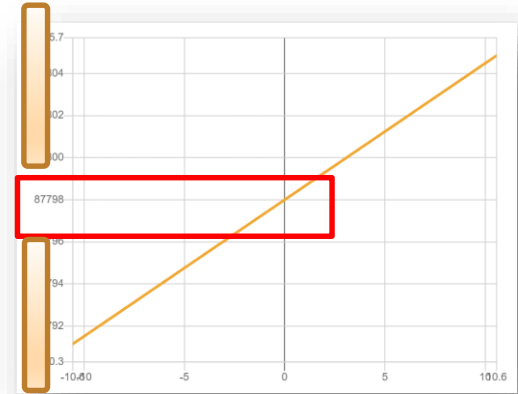
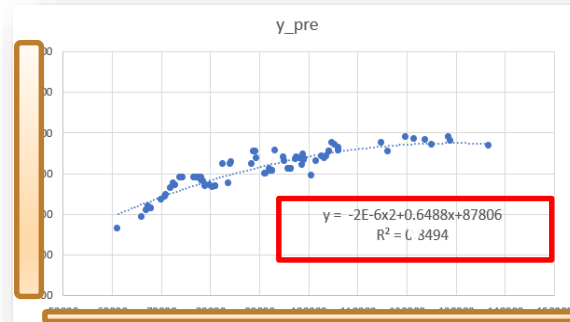
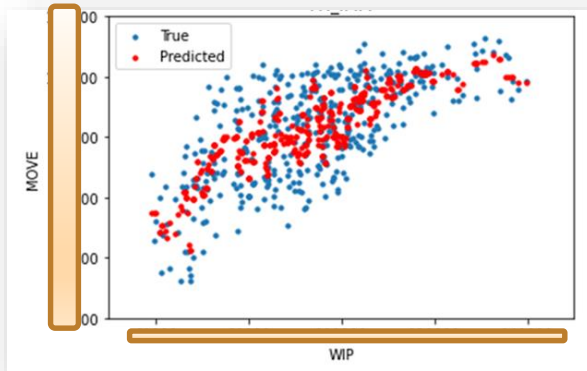


- For example, we chose Dry Etch. When the R Square of the KNN model is 94.48% and the MSE error is 0.011, we can know that the reasonable WIP is 12.95k. If the WIP exceeds 12.95k, the Move will approach saturation at 30k.

(MSE: 0.011, R2: 0.94, ideal WIP: 12.95k)

04. Experimental Results

This is one of the **PHOTO bottleneck work stations**, as the research object of this time.



- In PHOTO bottleneck stations. When the R Square of the KNN model is 84.94% and the MSE error is 0.044, we can know that the reasonable WIP is 87.8k. If the WIP exceeds 87.8k, the Move will approach saturation at 90k.

(**MSE: 0.044** , **R2: 0.8494** , **ideal WIP: 87.8k**)

04. Experimental Results

Conclusions and Future Research

| AREA | WSG | Ideal WIP |
|----------|------|-----------|
| PHOTO | XXXX | 87.8K |
| Dry Etch | XXXX | 12.95K |

1. The concept is extended to each WS of other Area, and the same analysis method is used to find the ideal WIP.
2. Add other factor analysis (MA 、 MU 、 idle 、 lost) ,using (Principal components analysis, PCA) Achieve data dimensionality reduction and find key factors.

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